

**IN THE CLAIMS**

Please enter the following amendments to the claims.

1. (currently amended) A copper polish slurry, comprising a mixture of:  
a surfactant containing an alkyltrimethylammonium cation; a chelating buffer system;  
an abrasive comprising silica; an oxidizer; and a corrosion inhibitor; wherein the slurry has a  
pH between 2.5 and 7.0.
2. (original) The slurry of Claim 1, wherein the surfactant comprises  
cetyltrimethylammonium bromide dissolved in the mixture.
3. (original) The slurry of Claim 1, wherein the surfactant comprises  
cetyltrimethylammonium cations and halogen anions.
4. (currently amended) The slurry of Claim 3, wherein [the abrasive comprises silica,  
the corrosion inhibitor comprises benzotriazole, and the oxidizer comprises hydrogen  
peroxide dissolved in the mixture.
5. (original) The slurry of Claim 1, wherein the chelating buffer system comprises  
ammonium bicitrate and potassium citrate dissolved in the mixture.

6. (original) The slurry of Claim 1, wherein the chelating buffer system is selected from the group consisting of citric acid/potassium citrate, and ammonium bicarbonate/potassium citrate.
7. (original) The slurry of Claim 1, wherein the corrosion inhibitor is selected from the group consisting of benzotriazole and cetyltrimethylammonium bromide.
8. (original) The slurry of Claim 1, wherein the surfactant comprises between 0.003M and 0.075M cetyltrimethylammonium bromide in the mixture.
9. (original) The slurry of Claim 1, wherein the surfactant comprises cetyltrimethylammonium hydroxide dissolved in the mixture.
10. (original) The slurry of Claim 1, wherein the surfactant comprises both cetyltrimethylammonium hydroxide and cetyltrimethylammonium bromide dissolved in the mixture.
11. (currently amended) A copper polish slurry, comprising in combination:  
water, a surfactant containing a alkyltrimethylammonium cation, a chelating buffer system, an abrasive comprising silica, an oxidizer, and a corrosion inhibitor, wherein the slurry has a pH between 2.5 and 7.0.
12. (currently amended) The slurry of Claim 11, wherein the abrasive compris[es]ing silica has [having] a surface area of 500 m<sup>2</sup>/g.

13. (original) The slurry of Claim 12, wherein the corrosion inhibitor is selected from the group consisting of benzotriazole and cetyltrimethylammonium bromide.
14. (previously amended) The slurry of Claim 11, wherein the corrosion inhibitor is benzotriazole and the surfactant is selected from the group consisting of cetyltrimethylammonium bromide and cetyltrimethylammonium hydroxide.
15. (previously amended) The slurry of Claim 11, wherein the slurry has a density of 1.03 g/ml.
16. (original) The slurry of Claim 11, wherein the oxidizer comprises hydrogen peroxide; and the chelating buffer system comprises citric acid and potassium citrate.